



SHEET 1 OF 1

INFORMATION DISCLOSURE  
CITATION IN AN  
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.  
**055071-0329**SERIAL NO.  
**10/756,830**APPLICANT  
**Doug van den BROEKE, et al.**FILING DATE  
**January 14, 2004**GROUP  
**2891**

## U.S. PATENT DOCUMENTS

| EXAMINER'S INITIALS | CITE NO. | Document Number<br>Number-Kind Code <sup>2</sup> (if known) | Publication Date<br>MM-DD-YYYY | Name of Patentee or Applicant of Cited Document | Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear |
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## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

| EXAMINER'S INITIALS | CITE NO. | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. |
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*C. Juerkett*

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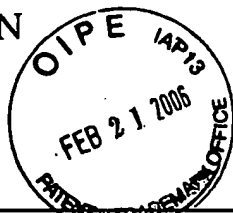
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| <i>CME</i>          |          | US 5,229,230  | 07/20/1993                     | Kamon   |   |
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| <i>CME</i>          |          | WO 02/03140 A1   | 01/10/2002                     | NUMERICAL TECHNOLOGIES, INC.                    |   | X           |  |
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